

ABSTRACT

A system and method of precisely adjusting the properties of a device using a gas cluster ion beam (GCIB) are described. Use of the invention permits the precise removal or addition of small amounts of material without significantly damaging or degrading the performance of the device. The system is capable of adjusting the properties of a single device or multiple devices and the devices may be processed serially, in small groups, or all at once. The system is also capable of delivering a single dose or a variety of doses depending on the amount of material needed to be removed or added to adjust the properties.

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